ranslation.

PATENT COOPERATION TREATY



PCT

INTERNATIONAL PRELIMINARY EXAMINATION REPORT

(PCT Article 36 and Rule 70)

Applicant's or agent's file reference NE-70135WO	FOR FURTHER ACTION See Notification of Transmittal of International Preliminary Examination Report (Form PCT/IPEA/416)					
International application No. PCT/JP2003/016034	International filing date (a		Priority date (day/month/year) 16 December 2002 (16.12.2002)			
International Patent Classification (IPC) or r H01L 29/812, 21/338	national classification and IF	PC				
Applicant NEC CORPORATION						
 This international preliminary examination report has been prepared by this International Preliminary Examining Authority and is transmitted to the applicant according to Article 36. 						
2. This REPORT consists of a total of sheets, including this cover sheet.						
This report is also accompanied by ANNEXES, i.e., sheets of the description, claims and/or drawings which have been amended and are the basis for this report and/or sheets containing rectifications made before this Authority (see Rule 70.16 and Section 607 of the Administrative Instructions under the PCT).						
These annexes consist of a total of sheets.						
3. This report contains indications re	lating to the following item:	s:				
Basis of the report						
II Priority	Priority					
Non-establishment of opinion with regard to novelty, inventive step and industrial applicability						
Lack of unity of i	I lock of unity of invention					
Document statement	The state of the s					
VI Certain documen	VI Certain documents cited					
VII Certain defects in	Certain defects in the international application					
VIII Certain observations on the international application						
Date of submission of the demand		Date of completic	on of this report			
15 December 2003 (15.12.2003)		06	September 2004 (06.09.2004)			
Name and mailing address of the IPEA/	JP	Authorized office	er			
Facsimile No.		Telephone No.				

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International application No.

PCT/JP2003/016034

I. Basis of the report						
1. With		the elements of the international application:*				
\boxtimes	the inter	rnational application as originally filed				
	the desc	cription:				
	pages	, as originally filed, filed with the demand				
	pages	filed with the letter of				
	pages	, filed with the letter of				
	the clai	ms:				
	pages	, as originally filed				
	pages	, as amended (together with any statement under Article 19				
	pages	, filed with the demand				
	pages	, filed with the letter of				
	the dra	wings: , as originally filed				
	pages					
	pages	, filed with the demand				
	pages	, filed with the letter of				
	the seque	ence listing part of the description:				
	pages	, as originally filed				
	pages	, filed with the demand				
	pages	, filed with the letter of				
		to the language, all the elements marked above were available or furnished to this Authority in the language in which onal application was filed, unless otherwise indicated under this item. nts were available or furnished to this Authority in the following language which is:				
	the la	nguage of a translation furnished for the purposes of international search (under Rule 23.1(b)).				
	the la	nguage of publication of the international application (under Rule 48.3(b)).				
	or 55.					
3. Wi	th regard	d to any nucleotide and/or amino acid sequence disclosed in the international application, the international examination was carried out on the basis of the sequence listing:				
	conta	ined in the international application in written form.				
	filed	together with the international application in computer readable form.				
		shed subsequently to this Authority in written form.				
	furni	shed subsequently to this Authority in computer readable form.				
	inter	statement that the subsequently furnished written sequence listing does not go beyond the disclosure in the national application as filed has been furnished.				
		statement that the information recorded in computer readable form is identical to the written sequence listing has furnished.				
4.	The	amendments have resulted in the cancellation of:				
		the description, pages				
!	П	the claims, Nos.				
1		the drawings, sheets/fig				
5.	This beyon	report has been established as if (some of) the amendments had not been made, since they have been considered to go nd the disclosure as filed, as indicated in the Supplemental Box (Rule 70.2(c)).**				
in	this rep	nt sheets which have been furnished to the receiving Office in response to an invitation under Article 14 are referred to Port as "originally filed" and are not annexed to this report since they do not contain amendments (Rule 70.16				
** Ar	ty replac	. ement sheet containing such amendments must be referred to under item 1 and annexed to this report.				

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V. Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement

citations and explanations supp			
1. Statement			YES
Novelty (N)	Claims	1-18	
	Claims		NO NO
Inventive step (IS)	Claims	4-7, 10-13, 17	YES
	Claims	1-3, 8-9, 14-16, 18	NО
Industrial applicability (IA)	Claims	1-18	YES
	Claims		ио
1			

2. Citations and explanations

Document 1: JP, 9-307097, A (SONY CORPORATION), 28 November 1997 (28.11.97), paragraphs [0031]~[0055], Figs. 4~9

Document 2: US, 2002-0005528, A1 (FUJITSU QUANTUM DEVICES LIMITED), 17 January

2002 (17.01.02), full text, all drawings

Document 3: JP, 2000-323495, A (SONY CORPORATION), 24 November 2000 (24.11.00),

full text, all drawings

Document 4: The Effect of Dielectric Stress on the Electrical Characteristics of AlGaN/GaN Heterostructure Field-Effect Transistors (HFETs) (W.S. TAN, ET. AL.), The 10th IEEE International Symposium on Electron Devices for Microwave and Optelectronic Applications, November 2002, pages 130-135

Document 5: JP, 2001-189324, A (RICOH COMPANY, LTD.), 10 July 2001 (10.07.01), full

text, all drawings

Document 6: JP, 2002-359256, A (FUJITSU LIMITED), 13 December 2002 (13.12.02), full text, all drawings

Claims 1-3

The subject matter of claims 1-3 does not involve an inventive step on account of document 1, document 2, and document 3 cited in the ISR.

Document 1 describes a field effect transistor comprising a group III nitride semiconductor structure with a heterojunction, source and drain electrodes formed at a separation on this semiconductor structure, a gate electrode disposed between the aforesaid source electrode and the aforesaid drain electrode, and an insulating film formed on the aforesaid group III nitride semiconductor layer. Document 2 describes a technique for increasing the voltage resistance of a field effect transistor by means of a gate electrode that has a field plate formed on an insulating film and extending in an eave-like manner to the drain electrode side. Document 3 describes a technique for reducing impurity diffusion depth randomness by covering the surface of a field effect transistor formed on a compound semiconductor with a laminated film consisting of a silicon nitride film 20 nm in thickness and a silicon dioxide film 20 nm in thickness. Employing the laminated film described in document 2 as the gate electrode of document 1 could easily be conceived by a person skilled in the art.

Claims 8-9

The subject matter of claim 8 does not involve an inventive step on account of document 1, document 2, document 4, and document 5 cited in the ISR.

Document 4 describes an example in which a silicon oxynitride film is used as the passivation film of an AlGaN/GaN heterojunction field effect transistor. Document 5 describes a technique for reducing parasitic capacitance by using an insulating film whose relative dielectric constant is 3.5 or less near the gate electrode. Employing the insulating film described in document 4 and document 5

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Supplemental Box

(To be used when the space in any of the preceding boxes is not sufficient)

Continuation of Box V.2:

as the insulating film of document 1 could easily be conceived by a person skilled in the art.

Claim 14-16, 18

The subject matter of claims 14-16 and 18 does not involve an inventive step on account of document 1 through document 6 cited in the ISR.

Document 6 describes a cap layer comprising a channel layer consisting of InxGal-xN, an electron supply layer consisting of AlyGal-yN, a contact layer consisting of an undoped AlGaN layer, and GaN. Employing the structure described in document 6 in the GaN field effect transistor of document 1 could easily be conceived by a person skilled in the art.

The subject matter of claims 4-7, 10-13, and 17 is neither described nor suggested in documents 1-6 cited in the ISR.